

PATENT

Atty. Dkt. No. APPM/005191.C1/ISMCORE/MCVD/PJS
Serial No.: 10/792,323

IN THE CLAIMS:

Please cancel claims 2, 5-7, 14-15, and 18-20, and amend the claims as follows:

1. (Currently Amended) An apparatus for vaporizing a solid precursor, comprising:

a housing defining an interior volume having an inlet for receiving a carrier gas and an outlet operably connected to an atomic layer deposition chamber;

at least two surfaces contained in the housing, wherein the at least two surfaces contain stainless steel, have a tantalum-containing the solid precursor applied thereto, and are spaced to allow passage of the carrier gas therebetween; and

at least one heating member contained in the housing, wherein the inlet is substantially perpendicular to the at least two surfaces.

2. (Cancelled)

3. (Currently Amended) The apparatus of claim [[2]] 1, wherein the at least two surfaces are selected from the group consisting of a baffle, a rod, a mesh and a grating.

4. (Original) The apparatus of claim 1, wherein the at least two surfaces have a form selected from the group consisting of an s-shape, a linear shape and a cone shape.

5-7. (Cancelled)

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